

STATUS OF THE WORK FOR THE EMULSIONS AFTER THE EXPOSURE AT GSI

A. Alexandrov, G. De Lellis, A. Di Crescenzo, <u>G. Galati</u>, A. Iuliano, A. Lauria, <u>M. C. Montesi</u>, A. Pastore, V. Tioukov

Università di Napoli "Federico II", INFN Napoli, INFN Bari

BRICK PREPARATION @ CERN

- 12	TARGET	Oxygen 200 MeV/n	Oxygen 400 MeV/n
	Carbon	GSI1	GSI3
	Polyethylene	GSI2	GSI4

4 BRICKS EXPOSURED AT GSI



520 emulsions have been exposed

WY BEAM TARGET	Oxygen 200 MeV/n	Oxygen 400 MeV/n
Carbon	GSI1	GSI3
Polyethylene	GSI2	GSI4

EMULSIONS DEVELOPMENT

 400 emulsions have been developed in Naples new dark room facility



 120 emulsions (stack 2) have undergone different thermal treatments and have been developed at LNGS



 All emulsions have been cleaned from silver residuals and have been treated with glycerine in order to minimize distortions and other problems due to the development and drying processes

EMULSIONS SCANNING

- Scanning began on 7th May
- One dedicated microscope in Naples
- Scanning parameter optimization on-going
- 30 emulsions (GSI2, stack 1) have been already scanned





Some Preliminary Results

PLATE 1

PLATE 30



X - Y microtrack distributions

Slope X microtrack distributions





Some Preliminary Results



BACK UP SLIDES

EMULSION SPECTROMETER DESIGN



DETECTOR STRUCTURE

	Oxyg	en 200 I	MeV/n	Оху	vgen 400 N	leV/n	
S1	C (30x1mm) / C2H4 (30x2mm) + 29 emu						
S2	Emu (36)						
S 3	Polyethylene (10x1mm)+10emu						
S4	W (10x0.5mm)+10emu						
S 5	W (15x0.9mm)+15emu						
S 6	Pb (20x1mm)+20emu		Pb (40x1mm)+40emu				
S1	S S3 S4 S	S5 S6		S1	S S3 S4 S5	S6	
	S1	S S3 S4 S5	5 S6				
1				S1	S S3 S S5	S 6	